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Name:

APJ ABDUL KALAM TECHNOLOGICAL UNIVERSITY

Third semester B.Tech examinations (S) September 2020

Course Code: EC203

Course Name: SOLID STATE DEVICES (EC,AE)

Max. Marks: 100

Duration: 3 Hours

Marks

(5)

(10)

PART A Answer any two full questions, each carries 15 marks.

- 1 a) Explain Hall effect? Derive the expression for carrier concentration and mobility (7) in terms of Hall voltage.
 - b) Explain the effect of temperature on mobility.
 - c) A Si sample is doped with 10^{16} cm⁻³ boron atoms and a certain number of (3) shallow donors. The Fermi level is 0.36 eV above *Ei*, at 300 K. What is the donor concentration N_d?

2 a) Derive the expression for diffusion current density in a semiconductor. (6)

- b) Show that diffusion length is the average length a carrier diffuse before (5) recombination.
- c) A Si sample with 10^{15} /cm³ donors is uniformly optically excited at room (4) temperature such that 10^{19} /cm³ electron-hole pairs are generated per second. Find the separation of the quasi-Fermi levels .Electron and hole lifetimes are both 10 μ s. $Dp = 12 \text{ cm}^2$ /s and $\mu_n = 1300 \text{ cm}^2$ /Vs.
- 3 a) Derive the law of mass action, starting from the fundamentals.
 - b) Consider Si doped with 2 x 10¹⁵ donors/cm³. Assume that $\tau_n = \tau_p = 5 \mu s$. Calculate (5) the recombination coefficient α_r for the low-level excitation. Using this value of recombination coefficient α_r , find the steady state excess carrier concentration $\Delta n = \Delta p$, if the sample is uniformly exposed to a steady state optical generation rate $g_{op} = 10^{19} \text{ EHP/cm}^3$ -s

PART B

Answer any two full questions, each carries 15 marks.

- 4 a) Derive the expression for contact potential and width of depletion region of an (10) abrupt PN junction at equilibrium.
 - b) A Si p+-n junction has a donor doping of 5×10^{16} cm⁻³ on the n side and a cross (5) sectional area of 10^{-3} cm². If $\tau_P = 1 \mu s$ and Dp = 10 cm²/s, calculate the current with a forward bias of 0.5 V at 300 K.
- 5 a) Derive the expression for junction capacitance and storage capacitance of a step (8) PN junction diode.
 - b) The work function of chromium is 4.5V. The dielectric constant and the electron (7) affinity of Si are 12 and 4.01V respectively. If the density of states $Nc=2.8 \times 10^{19}$

cm⁻³, compute the maximum electric field in the case of a junction formed by these two materials at 300 K, when the applied reverse voltage is 5V. Compute the junction capacitance per unit area for this case. Assume that Si is doped with 10^{17} /cm³ n type dopants.

- 6 a) With suitable energy band diagram explain a Schottky contact. (6)
 - b) Differentiate between Zener and avalanche breakdown mechanisms with (4) supporting diagrams
 - c) Draw the energy band diagram of a p-n junction at a) equilibrium b) Forward (5) bias c) Reverse bias.

PART C

Answer any two full questions, each carries 20 marks.

(10)

(5)

- 7 a) Derive an expression for base transport factor of a BJT.
 - b) Explain Early effect.
 - c) A pnp BJT has emitter (N_E), base (N_B), and collector (Nc) doping of 10^{20} cm⁻³, (5) 10^{18} cm⁻³ and 10^{17} cm⁻³ respectively, and a base width of 0.5 micron. Calculate the peak electric field at the CB junction, and the CB depletion capacitance per unit area for the normal active mode of operation with a V_{CB} = 50 V.
- 8 a) Draw and explain the C-V Characteristics of an Ideal MOS capacitor. Derive the (10) expression for threshold voltage.
 - b) For a MOSFET with $V_T = 1V$ and $W = 50 \ \mu m$, $L = 2 \ \mu m$, calculate the drain (5) current at

(i)
$$V_G = 5 V, V_D = 0.1 V$$

(ii) $V_G = 3V, V_D = 5V.$

Assume an electron channel mobility $\mu_n = 200 \text{ cm}^2$ /V-s, gate oxide thickness tox= 100Å, and the substrate is connected to the source.

- c) Draw and explain the subthreshold characteristics of an n-channel MOSFET. (5)
- 9 a) With the aid of necessary band diagrams, explain equilibrium, accumulation, (12) depletion and inversion stages of a MOS capacitor.
 - b) Explain the effect of real surfaces in the threshold voltage of a MOS capacitor. (4)
 - c) Explain the terms emitter injection efficiency and base transport factor of a BJT. (4)
